EUV
LITHO, INC.

2026 EUVL and Source Workshop

June 6 - 7, 2026 (Online Only Short Courses)
June 8 - 11, 2026 (Held In-Person only at Pauley Ballroom, UC Berkeley)

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FIRST CALL FOR PAPERS

2026 Extreme Ultraviolet Lithography (EUVL) and Source Workshop

The 2026 EUVL and Source Workshop, organized by EUV Litho, Inc. and co-hosted by EUV Tech, Molecular Foundry and the BETR Center at UC Berkeley, with support from the CH3IP consortium, will bring together the global community working on EUV Lithography, EUV and Soft X-ray Sources, and the supporting ecosystem that enables advances in semiconductor manufacturing, for continued extension of Moore's law. This workshop will cover the full spectrum of topics relevant to EUVL, high-NA EUVL and hyper-NA EUVL lithography, advanced source technology, materials, metrology, and the extension of lithography to wavelengths below 13.5 nm.

With EUVL scanners in high-volume manufacturing at the 3 nm and 2 nm nodes and beyond, this workshop will address lowering of the k1 value, enabling of infrastructure, addressing challenges for high-NA EUVL scanners, and exploring options beyond high-NA. The program will also highlight emerging directions that may support semiconductor manufacturing to 2030 and beyond, including hyper-NA lithography at 13.5 nm and Blue-X lithography at wavelengths from 2 to 7 nm. Papers are also invited on the use of AI and machine learning for semiconductor technology development.

In addition to technical presentations, the program will incorporate a Supplier Showcase that brings together suppliers, researchers, and end-users for detailed discussions of technologies, specifications and challenges. This integrated format fosters close interaction among all participants and encourages the exchange of ideas across the EUV and source communities.

List of Topics

Abstracts are invited across all areas of relevance to EUVL, EUV and Soft X-ray Sources and Next-Generation Lithography. Topics include, but are not limited to:

- EUV and metrology source technology including LPP, DPP, HHG, FEL, synchrotrons, and new concepts
- High power source development, source diagnostics, and source metrology

- Optics and optical design, including projection optics, collector optics, and multilayer coatings
- EUV mask technology, including pellicles, absorber materials, cleaning, and defect mitigation
- Resists and underlayers, stochastic effects, pattern collapse, and line edge roughness
- Contamination, cleaning strategies, and lifetime management for sources, masks, and optics
- Metrology and inspection for masks, resists, optics, stochastic analysis, and pattern fidelity
- Patterning, process integration, and design for manufacturability
- Lithography at wavelengths below 13.5 nm (Blue-X, 2 to 7 nm), including sources, optics, optical design, masks, and photoresists
- Shorter wavelength source applications for scanners, metrology, microscopy, and analytical instrumentation
- Theoretical and modeling studies relevant to EUVL, sources, and next-generation lithography
- Applications of AI and machine learning across lithography, patterning, source science, and semiconductor manufacturing technology

Agenda Overview

The June 6-7, 2026 short courses will be held online only. The June 8-11, 2026 workshop will be held in In-person only at the Pauley Ballroom, UC Berkeley, Berkeley, California, USA

- June 6–7, 2026: Two online short courses
- June 8, 2026 (morning and afternoon): Blue-X Technical Working Group (TWG) meeting (members only), followed by a joint reception for the Blue-X TWG and *EUVL and Source Workshop* attendees
- June 8–11, 2026
  In-person technical presentations, poster session, reception, and conference dinner for the *EUVL and Source Workshop*

Instructions for Submissions

- Submit an abstract of less than 200 words
- Indicate whether you prefer an oral or poster presentation
- Use the abstract template (available at euvlitho.com) and email submissions to info@euvlitho.com

Abstract Submission Deadline: Friday, March 20, 2026

For logistics questions, email **info@euvlitho.com**

Workshop Chair

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